

SiPM characterization, concept and measurements

SiPM workshop LIP, April 18, 2012

Thomas Schweizer







Principle of SiPM and some basic properties

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Concept of SiPM



Mode







Summing many cells

Problem: Optical crosstalk Light produced in avalanche process



When an avalanche is triggered in one SPAD we have:

- Secondary photons emission due to the avalanche current
- Photons propagation throughout the chip
- Secondary photon detection by a nearby detector





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SiPM Spectrum with afterpulses

- Deviation from Poisson statistics
- Measurement of optical crosstalk probability:
 - Count Pedestal and 1. & 2. Photoelectron peak
 - Calculate deviation of 2. peak from Poisson
- → Long tail in SiPM pulse hight distribution vs threshold



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Measurement of photons from avalanche process (Max Knötig)

- Illuminate one SiPM cell with small laser spot
- Observe emission of photons from avalanche process (microscope)



laser spot FWHM 2μm

Thomas Schweizer, SiPM workshop LIP, April 18, 2012 Wednesday, April 18, 2012 Light emission from neighbouring cells

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Alternative measurement of optical crosstalk (Max Knötig)

- Measure light in neighbouring cells with Microscope
- Good agreement with conventional method !



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'Delayed' optical crosstalk in SiPM

- Photons are generated during avalanche process
- They create photoelectrons in bulk material
- Electrons drift back into the avalanche region and trigger cell
- Time characteristic: 1ns-20ns



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Afterpulses in Silicon

- Impurities and defects in the silicon lattice may have irregular behaviour
- Carriers during an avalanche discharge are trapped and released later in time
- Time characteristics: up to 100ns



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Suppressing afterpulses

- Afterpulse-excitations have a lifetime of up to 100ns.
- By using quenching resistors of 1MOhm the recovery time of one cell that has fired increases to about 1usec (recharging time of capacitance)

- Afterpulses do not get a chance to trigger the same cell twice.
- Hamamatsu uses 100kOhm quenching resistor. The recharging time is faster and afterpulses appear.

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Counting crosstalk in QE measurement: Measured and real PDE: Hamamatsu MPPC



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Solutions to reduce optical crosstalk: Introduce trenches

- Introduce
 optical barrier
 between cells
- block the instantanous photon crosstalk





Solutions to reduce 'delayed' optical crosstalk: Block drifting electrons

- Introduce
 second p-n
 junction
- Potential barrier
 will block drifting
 electrons



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Arrival time of 'instantaneous' and 'delayed' optical cross-talk



Interesting experiment: Mirror in front of Dolgoshein-SiPM





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MEPhI - MPI for Physics R&D collaboration and cooperation with PerkinElmer Industries (now EXCELITAS)

Developing UV sensitive SiPMs with extremely high PDE,

Extremely low crosstalk and low dark rate



Pioneer and great Leader: Prof., member of Russian Academy of Sciences Boris Dolgoshein 1930-2010 SiPM Sizes 1x1 and 3x3 mm² µ-cell pitch 50 and 100 µm Geom. Eff. 40-80%

16-17 February 2011

B. Dolgoshein, R. Mirzoyan, E. Popova, P. Buzhan, PEI, et al.,

General specifications of SiPM

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Recovery time of fired cell (--> suppression of afterpulses)

Recovery time of SINGLE pixel: C(pix)xR(pix)-->20ns.....a few mks



B.Dolgoshein,LIGHT06

Jelena Ninkovic Wednesday, April 18, 2012

Gain and PDE as function of overvoltage (Perkin-Ellmer-SiPM as example)

A PDE and gain of a 1x1 mm² SiPM produced by PEI measured at +20°C

Overvoltage = operational voltage - breakdown voltage



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Temperature dependence of dark rate





Cross talk comparison of different SiPM



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Signal timing for $3x3mm^2$ SiPM sample 40ps FWHM laser pulses, λ =405nm, single photon mode T = -40° C



Samples for evaluation may become available very soon

16-17 February 2011

B. Dolgoshein, R. Mirzoyan, E. Popova, P. Buzhan, PEI, et al.,

General properties of SiPM



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Measurement methods for characterization

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Measurements of Hamamatsu SiPM: Pulse shape (HPD and SiPM)



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Passive shaping (simple capacitive coupling into 50 Ohms) reduces the fall time (needed for reduction of pile-up)



Measurement of QE

Monitor the photon detection efficiency:



 Compare SiPM PDE with calibrated reference detector such as HPD

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Measurements using pulses and FADC

- Illumination of SiPM and reference detector with same pulsed light flux
- Measurement of counts in pedestal and 1. PhE peak
- Calculation of Poisson mean
- Measurement of crosstalk of SiPM by 2. Peak
- Correction of mean counts of both detectors due to (detector dependent) losses
- Calculation of SiPM PDE by comparison of QE and mean counts

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Voltage scan Hamamatsu



Voltage scan Dolgoshein W5N42 3x3mm



Measurements with discriminator

Illuminate SiPM with continuous light flux



Need a calibrated reference detector --> PIN diode

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Measurements with Hamamatsu SiPM: Counting mode with signal shaping

 SiPM signal (with shaping) and discriminator (25ns pulse width)



Pile-up and dead time at high rate: --> cross talk correction



Measurement of gain and crosstalk by threshold scan



Cameras with SiPM

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FACT camera with 1440 SiPM (First G-APD camera telescope)



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Testcamera with cooling plate for possible future AUGER fluorescence detector





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Thermal simulations: Condensation



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Temperature distribution at window --> will get condensation

-> gravity !!-> double glas window





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Reduce reflectivity of entrance window

 Antireflective coatings with amorphous flouropolymer resin (Teflon) (companies: Cytop, DuPont)



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Significant reduction of reflection by moth eye structure



Sketch of readout and slow control for SiPM camera



Development of a lowcost-lowpower readout with 64 programmable discriminators

- Front-end ASIC: MAROC III
- Programmable shaping time
- Programmable threshold
- Charge sensitive inputs, sensitivity 15 fC
- PWR TestPulse Bias VthMON ChargeOut ASICCON TEMP JTAG **Bias Control ADC** TEMP PRO USB switch SERDES SFP 64 ch MPPC ASIC 64 MAPD3N FPG/ SFP SERDES SYNC CLK **Bias Control DAC** Cold Plate TEMP CLKEXT Humidity SUM8 **RS232**

- On-Board FPGA
- optical link transmission
- USB2 output



Online calibration (and adjustment) of both: Gain and PDE:

Monitor gain and (relative) PDE with discriminator only



 In case of rate increase the point of 50% remains at the same threshold (--> gain or amplitude of pulses)

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Optimize light collection on SiPM

- Perfect' Winston cone
- Si has refractive index 3.6-3.8
 --> strong reflection
- Covered by SiO2
- Additional protection layer with a resin
- Need an additional antireflective treatment
- PMMA layer with motheye plasma etching



SiPM light guides for test camera



Reflectivity of coated 3M-Vikuity-foil



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Thanks

Quantum efficiency of different SiPM



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